

Electromechanical coupling coefficient of isotropic sample with a marked electrostriction

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Abstract

Isotropic sample of single ferroelectric crystal (STO) with cubic symmetry or the epitaxial BSTO film does not exhibit a piezoelectric effect, but is characterized by electrostriction. The induced piezoelectric effect occurs under the dc electric field. Using electromechanical equations for this material in presence of both the dc and ac electric field makes possible to describe the transformation of energy of electromagnetic field into acoustic oscillations. The transformation intensity is estimated by the electromechanical coupling coefficient determined as the ratio of the energy of alternating electromechanical interaction to the geometric mean of alternating electrical and mechanical energy. For the induced piezoeffect, the analytical model for the electromechanical coupling coefficient is obtained using phenomenological description of the dc electric field dependence of the dielectric permittivity. There is a maximum on the dependence of the electromechanical coupling coefficient on the dc field. The value of maximum and related dc field depend on the ferroelectric film quality.

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1. Introduction

High-Q microwave acoustic resonators were suggested and employed in microwave high quality filters.^{1–3} In these resonators, materials with highly pronounced piezoelectric effect are used. In the case of SrTiO_3 (STO) and BaSrTiO_3 (BSTO) materials with centro-symmetric cubic lattice no piezo-effect should be observed. Very small piezoelectric effect in STO was revealed and explained by the influence of mechanical stress and slightly non-cubic structure.⁴ At the same time the distinctive peaks of loss factor of the parallel-plate varactor based on a thin BSTO film⁵ were observed in ref.⁶ The peak height was correlated with the dc biasing voltage applied to the varactor. The nature of the peaks was explained by the induced piezoelectric hypersound generation.⁷ The hypersound generation on STO and BSTO materials was also observed in refs.^{8–10} and theoretically estimated in refs.^{11,12} The explanation was based on the model of the induced piezo-effect due to electrostriction in the material existing by applying dc biasing field.

The most promising microwave application of the effect observed is using the induced piezoelectricity for tuning res-

onant frequency of the acoustic resonator.⁷ The intensity of the bulk acoustic waves in the BSTO or STO acoustic resonator is determined by the electromechanical coupling, which is estimated numerically by the electromechanical coupling coefficient.^{1,13}

The goal of this paper is to develop a model of the induced piezoelectricity in non-piezoelectric material described by the electromechanical coupling coefficient depending on the dc biasing field.

2. Electromechanical coupling coefficient

For a description of the electromechanical phenomena in the crystals, the expansion of the free energy over powers of the dielectric polarization and the mechanical deformation can be used.^{14,15} The expansion contains components of the electric field vector E_m , components of the permittivity tensor ϵ_{ij} , components of the strain tensor σ_{ij} , the compliance tensor components s_{ijkl} , and the components of the electrostriction tensor R_{ijmn} . We suggest that the piezoelectric modulus is zero. The tensor $||R||$ is a function of the biasing field. The most convenient form of the electrostriction tensor is the tensor $||Q||$, which enters into the free energy equation in the form of $Q_{ijkl}D_iD_j\sigma_{kl}$. For BSTO and other perovskite type crystals or ceramics the

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terms of the tensors of the electrostriction Q_{ijpq} do not depend on the biasing field and slightly depend on temperature in both the ferroelectric state and in the paraelectric state¹⁶ and can be taken constant for a practical use.

In order to simplify the problem, we assume that the BSTO film is isotropic. In an isotropic medium the permittivity tensor is converted into a scalar $\varepsilon_{mn} = \varepsilon_0 \varepsilon_r$, where ε_r is the relative permittivity of the medium, ε_0 is the permittivity of the free space. The electrostriction tensor $||Q||$ has two independent components: the diagonal component Q and the off-diagonal component Q_k . For the BSTO, $Q \cong 0.066 \text{ m}^4/\text{C}^2$ and $Q_k = 0.01 \text{ m}^4/\text{C}^2$.¹⁶ For an isotropic medium¹⁴

$$R = Q \cdot \varepsilon_0^2 \varepsilon_r^2 \quad R_k = Q_k \cdot \varepsilon_0^2 \varepsilon_r^2. \quad (1)$$

Let us assume that the electric field vector \mathbf{E} consists of ac and dc components: $\mathbf{E} = \mathbf{E}^{\text{ac}} + \mathbf{E}^{\text{dc}}$. The free energy can be taken as a sum of three terms:

$$F_{\Sigma} = F_0 + F^{(\text{dc})} + F^{(\text{ac})}, \quad (2)$$

where $F^{(\text{dc})}$ and $F^{(\text{ac})}$ are contributions into the free energy by dc and ac electric field components, respectively. If no dispersion of $\varepsilon(\omega)$ is observed in the range of operational frequency, the total ac free energy for an isotropic medium is

$$F^{(\text{ac})} = \frac{1}{2} \varepsilon \cdot (E^{(\text{ac})})^2 + \frac{1}{2} s \cdot (\sigma^{(\text{ac})})^2 + R \cdot E^{(\text{dc})} E^{(\text{ac})} \sigma^{(\text{ac})} + \dots, \quad (3)$$

where s and R are the diagonal terms of the tensors of the compliance and the electrostriction. The first term in (3) is the energy density of alternating electric field, the second term is the energy density of alternating mechanical strain, and the third term is the energy density of alternating electromechanical interaction.

In accordance with,¹³ the electromechanical coupling coefficient can be presented as

$$K = \frac{|R \cdot E^{(\text{dc})} E^{(\text{ac})} \sigma^{(\text{ac})}|}{\sqrt{\varepsilon \cdot (E^{(\text{ac})})^2 s \cdot (\sigma^{(\text{ac})})^2}}. \quad (4)$$

Using Eq. (1), we replace the diagonal terms of the tensors of electrostriction R by the term Q and obtain:

$$K(E^{(\text{dc})}) = \frac{Q \cdot |E^{(\text{dc})}| \cdot \varepsilon_r (E^{(\text{dc})})^2 \varepsilon_0^2}{\sqrt{\varepsilon_r (E^{(\text{dc})}) \varepsilon_0 s}}. \quad (5)$$

In this equation, the electromechanical coupling coefficient depends on the dc electric field directly and indirectly via the dielectric permittivity of the ferroelectric material $\varepsilon_r(E^{(\text{dc})})$, which depends strongly on the biasing field. The results of simulation of the electromechanical coupling coefficient as a function of the dc biasing field for typical dielectric and acoustic parameters of the BSTO film are shown in Fig. 1. In the simulation, the correct model¹⁷ of the dielectric response $\varepsilon_r(E^{(\text{dc})})$ of the ferroelectric material was used. The most important feature of the results obtained is the presence of the maximum on the characteristics. The position of the maximum and related value of the dc field depends on the BSTO film quality determined by the model parameter ξ_S : the higher ξ_S , the lower is the film quality,

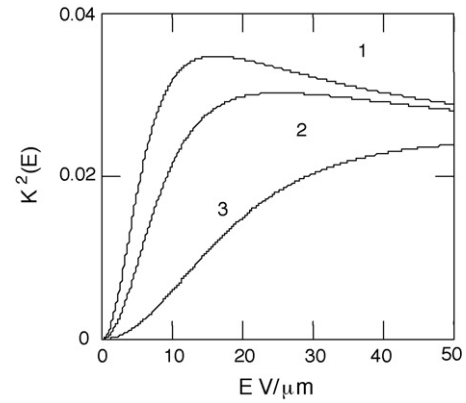


Fig. 1. Electromechanical coupling coefficient vs. dc biasing field for the BSTO film with the acoustic parameters $Q \cong 0.066 \text{ m}^4/\text{C}^2$ and $s = 6.12 \cdot 10^{-12} \text{ m}^2/\text{N}$ and the dielectric model¹⁷ parameters: $E_N = 440 \text{ kV/cm}$, $T_C = 240 \text{ K}$, $\varepsilon_{00} = 430$, $\theta_F = 175 \text{ K}$: $\xi_S = 1$ (1), $\xi_S = 2$ (2), $\xi_S = 5$ (3).

the higher dc field corresponds to the maximum value of the coupling coefficient, and the smaller is this maximum value of K . Evidently, a high quality ferroelectric material should be used for a highly pronounced induced piezoelectric effect.

3. Tuneability of the BSTO based bulk acoustic resonator

A thin film bulk acoustic resonator (TFBAR) is formed by a thin piezoelectric film, in which the bulk acoustic oscillations are excited. In the case of the BSTO film, the acoustic oscillations are caused by the electric voltage applied to the electrodes on the surfaces of the film in presence of the dc field providing the induced piezoeffect. In general case, the active acoustic region is terminated in input acoustic impedance of the electrodes Z_L and Z_R on the left and right sides of the structure (Fig. 2). The acoustic resonator modeling¹ gives the following equation for the input electrical impedance of the acoustic resonator:

$$Z_{\text{eq}} = \frac{1}{Y_{\text{eq}}} = \frac{1}{i\omega C} \left[1 - K^2 \frac{\tan \phi}{\phi} \cdot \frac{(Z_R + Z_L) \cos^2 \phi + i \sin 2\phi}{(Z_R + Z_L) \cos 2\phi + i(Z_R Z_L + 1) \sin 2\phi} \right], \quad (6)$$

where C is the capacitance of the parallel plate capacitor formed by the resonator structure and ϕ is the acoustic length dependent

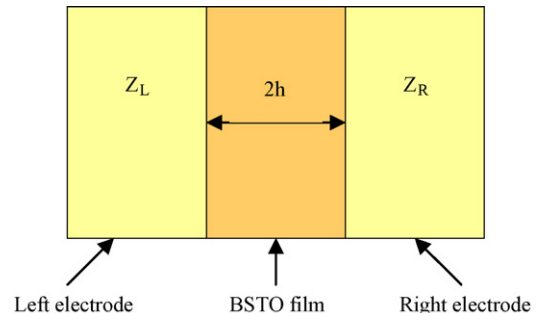


Fig. 2. Structure of a tuneable bulk acoustic resonator.

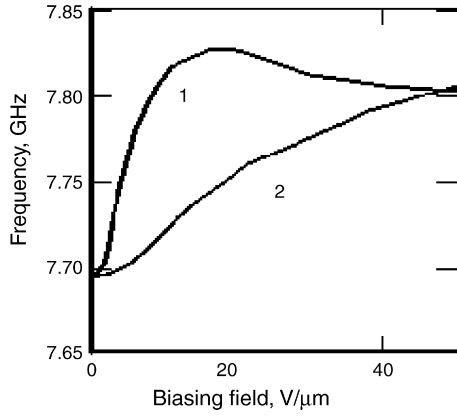


Fig. 3. Resonant frequency of the antiresonance as a function of the dc biasing field for different crystallographic quality of the BSTO film: $\xi_S = 1$ (1), $\xi_S = 5$ (2). Other parameters are the same as in legend to Fig. 1.

on the biasing voltage:

$$\phi(E^{(dc)}) = k(E^{(dc)}) \cdot h = \frac{\omega}{V_{ac}(E^{(dc)})} \cdot h \quad (7)$$

$$V_{ac}(E^{(dc)}) = V_{ac}^{(0)} \cdot \sqrt{1 + K(E^{(dc)})^2}, \quad V_{ac}^{(0)} = \sqrt{\frac{c}{\rho}} \quad (8)$$

Here c is the elastic constant and ρ is the material density.

One can write the following cause–effect consecution:

$$K(E^{(dc)}) \rightarrow V_{ac}(E^{(dc)}) \rightarrow k(E^{(dc)}) \rightarrow \phi(E^{(dc)}), \quad (9)$$

The acoustic length $\phi(E^{(dc)})$ is further used for a description of resonant conditions.

In line with (6), there are two specific cases when $Z_{in} = 0$ related to the resonance and $Z_{in} = \infty$ related to the antiresonance. Solving (6) for these two cases one can find $\phi_{res}(E^{(dc)})$ and $\phi_{ares}(E^{(dc)})$ for resonance and antiresonance. The corresponding frequencies are

$$f_{res} = \frac{V_{ac}(E^{(dc)})}{\lambda_{ac}^{res}(E^{(dc)})} \quad \text{with} \quad \lambda_{ac}^{res}(E^{(dc)}) = \frac{2\pi h}{\phi_{res}(E^{(dc)})} \quad (10)$$

$$f_{ares} = \frac{V_{ac}(E^{(dc)})}{\lambda_{ac}^{ares}(E^{(dc)})} \quad \text{with} \quad \lambda_{ac}^{ares}(E^{(dc)}) = \frac{2\pi h}{\phi_{ares}(E^{(dc)})} \quad (11)$$

In the case of perfect boundary conditions $Z_L = Z_R = 0$, the Eq. (6) is simplified and the resonant acoustic length for the resonance $\phi_{res}(E^{(dc)})$ can be found from the equation:

$$K(E^{(dc)})^2 = \frac{\tan \phi_{res}(E^{(dc)})}{\phi_{res}(E^{(dc)})}, \quad (12)$$

and $\phi_{ares}(E^{(dc)})$ for the antiresonance is found from

$$\tan \phi_{ares}(E^{(dc)}) = \infty \rightarrow \phi_{ares}(E^{(dc)}) = \frac{\pi}{2}. \quad (13)$$

The results of modeling the resonant frequency dependence on the dc biasing field (antiresonance) are presented in Fig. 3 for the BSTO film with $V_{ac}(0) = 8000$ m/s, attenuation constant $\alpha = 0.001$, and the thickness of the film $2h = 500$ nm. The results are shown for the first antiresonant mode. For the resonance,

the frequency shift is slightly less as compared with the antiresonance. In the case of a real system of electrodes,⁷ the input impedance exhibits multiresonance tuneable response for the both resonance and antiresonance containing additional spurious responses related to the acoustic resonances in the whole multi-electrode structure. The tuneability of the BSTO response is less pronounced in this case. Evidently, a special trouble should be taken to provide highly reflective boundary conditions. For this, the Bragg reflection structure or membrane structure made by micromachinary technique can be used.

4. Conclusion

Modeling of excitation of the acoustic wave oscillations by the induced piezoeffect in ferroelectric materials (BSTO film) revealed that there is a maximum in the dependence of the electromechanical coupling coefficient on the dc electric field. The value of maximum and the related dc field depend on the ferroelectric film quality. The tuneability of the resonant frequencies of resonance and antiresonance was demonstrated. The model developed can be used as a basis of a design of a tuneable bulk acoustic resonator for microwave application.

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